

Hyungjun Kim

List of Publications by Year in descending order

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280
papers

12,882
citations

20817

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h-index

30922

102
g-index

293
all docs

293
docs citations

293
times ranked

17071
citing authors

#	ARTICLE	IF	CITATIONS
1	On the importance of the electric double layer structure in aqueous electrocatalysis. <i>Nature Communications</i> , 2022, 13, 174.	12.8	92
2	BitBlade: Energy-Efficient Variable Bit-Precision Hardware Accelerator for Quantized Neural Networks. <i>IEEE Journal of Solid-State Circuits</i> , 2022, 57, 1924-1935.	5.4	11
3	A bimetallic PdCu@Fe ₃ O ₄ catalyst with an optimal d-band centre for selective N-methylation of aromatic amines with methanol. <i>Catalysis Science and Technology</i> , 2022, 12, 3524-3533.	4.1	6
4	Enhanced Light Emission through Symmetry Engineering of Halide Perovskites. <i>Journal of the American Chemical Society</i> , 2022, 144, 297-305.	13.7	5
5	Development of RuS ₂ for near-infrared photodetector by atomic layer deposition and post-sulfurization. <i>Rare Metals</i> , 2022, 41, 3086-3099.	7.1	4
6	MoS ₂ doping by atomic layer deposition of high-k dielectrics using alcohol as process oxidants. <i>Applied Surface Science</i> , 2021, 541, 148504.	6.1	6
7	PE-ALD of Ge _{1-x} S _x amorphous chalcogenide alloys for OTS applications. <i>Journal of Materials Chemistry C</i> , 2021, 9, 6006-6013.	5.5	12
8	Unipolar stroke, electroosmotic pump carbon nanotube yarn muscles. <i>Science</i> , 2021, 371, 494-498.	12.6	110
9	Dynamic Transformation of a Ag ⁺ -Coordinated Supramolecular Nanostructure from a 1D Needle to a 1D Helical Tube via a 2D Ribbon Accompanying the Conversion of Complex Structures. <i>Journal of the American Chemical Society</i> , 2021, 143, 3113-3123.	13.7	24
10	Selective electrochemical reduction of nitric oxide to hydroxylamine by atomically dispersed iron catalyst. <i>Nature Communications</i> , 2021, 12, 1856.	12.8	106
11	2D MoS ₂ Charge Injection Memory Transistors Utilizing Hetero-Stack SiO ₂ /HfO ₂ Dielectrics and Oxide Interface Traps. <i>Advanced Electronic Materials</i> , 2021, 7, 2100074.	5.1	8
12	Atomic-Layer-Deposition-Based 2D Transition Metal Chalcogenides: Synthesis, Modulation, and Applications. <i>Advanced Materials</i> , 2021, 33, e2005907.	21.0	42
13	Lattice Engineering to Simultaneously Control the Defect/Stacking Structures of Layered Double Hydroxide Nanosheets to Optimize Their Energy Functionalities. <i>ACS Nano</i> , 2021, 15, 8306-8318.	14.6	49
14	Hydrogen Barriers Based on Chemical Trapping Using Chemically Modulated Al ₂ O ₃ Grown by Atomic Layer Deposition for InGaZnO Thin-Film Transistors. <i>ACS Applied Materials & Interfaces</i> , 2021, 13, 20349-20360.	8.0	15
15	Femtosecond Quantum Dynamics of Excited-State Evolution of Halide Perovskites: Quantum Chaos of Molecular Cations. <i>Journal of Physical Chemistry C</i> , 2021, 125, 10676-10684.	3.1	1
16	Microbially Guided Discovery and Biosynthesis of Biologically Active Natural Products. <i>ACS Synthetic Biology</i> , 2021, 10, 1505-1519.	3.8	11
17	Interface Defect Engineering of a Large-Scale CVD-Grown MoS ₂ Monolayer via Residual Sodium at the SiO ₂ /Si Substrate. <i>Advanced Materials Interfaces</i> , 2021, 8, 2100428.	3.7	14
18	Physicochemical Understanding of the Impact of Pore Environment and Species of Adsorbates on Adsorption Behaviour. <i>Angewandte Chemie</i> , 2021, 133, 20667-20673.	2.0	1

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19	Simultaneous Enhanced Efficiency and Stability of Perovskite Solar Cells Using Adhesive Fluorinated Polymer Interfacial Material. <i>ACS Applied Materials & Interfaces</i> , 2021, 13, 35595-35605.	8.0	20
20	Physicochemical Understanding of the Impact of Pore Environment and Species of Adsorbates on Adsorption Behaviour. <i>Angewandte Chemie - International Edition</i> , 2021, 60, 20504-20510.	13.8	8
21	Interface Defect Engineering of MoS ₂ Monolayer: Interface Defect Engineering of a Large-scale CVD-grown MoS ₂ Monolayer via Residual Sodium at the SiO ₂ /Si Substrate (<i>Adv. Mater. Interfaces</i> 14/2021). <i>Advanced Materials Interfaces</i> , 2021, 8, 2170080.	3.7	1
22	Assessment and prediction of band edge locations of nitrides using a self-consistent hybrid functional. <i>Journal of Chemical Physics</i> , 2021, 155, 024120.	3.0	1
23	Synthesis and Application of AgBiS ₂ and Ag ₂ S Nanoinks for the Production of IR Photodetectors. <i>ACS Omega</i> , 2021, 6, 20710-20718.	3.5	19
24	Reaction Mechanisms of Non-hydrolytic Atomic Layer Deposition of Al ₂ O ₃ with a Series of Alcohol Oxidants. <i>Journal of Physical Chemistry C</i> , 2021, 125, 18151-18160.	3.1	6
25	Growth mechanism and electrical properties of tungsten films deposited by plasma-enhanced atomic layer deposition with chloride and metal organic precursors. <i>Applied Surface Science</i> , 2021, 568, 150939.	6.1	5
26	Optical Reflection from Unforbidden Diffraction of Block Copolymer Templated Gyroid Films. <i>ACS Macro Letters</i> , 2021, 10, 1609-1615.	4.8	6
27	Group IV Transition Metal (M = Zr, Hf) Precursors for High- ρ Metal Oxide Thin Films. <i>Inorganic Chemistry</i> , 2021, 60, 17722-17732.	4.0	4
28	Photocurrent Enhancement of PtSe ₂ Photodetectors by Using Au Nanorods. <i>Photonics</i> , 2021, 8, 505.	2.0	7
29	<i>In Situ</i> Mapping and Local Negative Uptake Behavior of Adsorbates in Individual Pores of Metal-Organic Frameworks. <i>Journal of the American Chemical Society</i> , 2021, 143, 20747-20757.	13.7	5
30	uMBD: A Materials-Ready Dispersion Correction That Uniformly Treats Metallic, Ionic, and van der Waals Bonding. <i>Journal of the American Chemical Society</i> , 2020, 142, 2346-2354.	13.7	29
31	Surface Energy Change of Atomic-Scale Metal Oxide Thin Films by Phase Transformation. <i>ACS Nano</i> , 2020, 14, 676-687.	14.6	10
32	Comparative study on atomic layer deposition of HfO ₂ via substitution of ligand structure with cyclopentadiene. <i>Journal of Materials Chemistry C</i> , 2020, 8, 1344-1352.	5.5	24
33	Rate performance enhancement of lithium-ion battery using precise thickness-controllable-carbon-coated titanium dioxide nanowire array electrode via atomic layer deposition. <i>Electrochimica Acta</i> , 2020, 334, 135596.	5.2	9
34	Atomic layer deposition for nonconventional nanomaterials and their applications. <i>Journal of Materials Research</i> , 2020, 35, 656-680.	2.6	9
35	A General Strategy to Atomically Dispersed Precious Metal Catalysts for Unravelling Their Catalytic Trends for Oxygen Reduction Reaction. <i>ACS Nano</i> , 2020, 14, 1990-2001.	14.6	116
36	Activity-Stability Relationship in Au@Pt Nanoparticles for Electrocatalysis. <i>ACS Energy Letters</i> , 2020, 5, 2827-2834.	17.4	49

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37	Self-Powered Gas Sensors: 2D Transition Metal Dichalcogenide Heterostructures for p- and n-Type Photovoltaic Self-Powered Gas Sensor (Adv. Funct. Mater. 43/2020). Advanced Functional Materials, 2020, 30, 2070284.	14.9	1
38	Thermal Transformation of Molecular Ni ²⁺ to Ni ⁴⁺ Sites for Enhanced CO ₂ Electroreduction Activity. ACS Catalysis, 2020, 10, 10920-10931.	11.2	81
39	Intermetallic PtCu Nanoframes as Efficient Oxygen Reduction Electrocatalysts. Nano Letters, 2020, 20, 7413-7421.	9.1	109
40	Fe _x Ni _{2-x} P Alloy Nanocatalysts with Electron-Deficient Phosphorus Enhancing the Hydrogen Evolution Reaction in Acidic Media. ACS Catalysis, 2020, 10, 11665-11673.	11.2	41
41	2D Transition Metal Dichalcogenide Heterostructures for p- and n-Type Photovoltaic Self-Powered Gas Sensor. Advanced Functional Materials, 2020, 30, 2003360.	14.9	102
42	Electric Field Mediated Selectivity Switching of Electrochemical CO ₂ Reduction from Formate to CO on Carbon Supported Sn. ACS Energy Letters, 2020, 5, 2987-2994.	17.4	41
43	Water Slippage on Graphitic and Metallic Surfaces: Impact of the Surface Packing Structure and Electron Density Tail. Journal of Physical Chemistry C, 2020, 124, 11392-11400.	3.1	6
44	Atomic layer deposition of a uniform thin film on two-dimensional transition metal dichalcogenides. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, .	2.1	25
45	Monolayered g-C ₃ N ₄ nanosheet as an emerging cationic building block for bifunctional 2D superlattice hybrid catalysts with controlled defect structures. Applied Catalysis B: Environmental, 2020, 277, 119191.	20.2	56
46	Dynamic metal-polymer interaction for the design of chemoselective and long-lived hydrogenation catalysts. Science Advances, 2020, 6, eabb7369.	10.3	53
47	Synthesis of a Hybrid Nanostructure of ZnO-Decorated MoS ₂ by Atomic Layer Deposition. ACS Nano, 2020, 14, 1757-1769.	14.6	29
48	Improved interface quality of atomic-layer-deposited ZrO ₂ metal-insulator-metal capacitors with Ru bottom electrodes. Thin Solid Films, 2020, 701, 137950.	1.8	14
49	Thermodynamics of Multicomponent Perovskites: A Guide to Highly Efficient and Stable Solar Cell Materials. Chemistry of Materials, 2020, 32, 4265-4272.	6.7	26
50	The Precursor Adsorption Mechanism, Growth Characteristics and Electrical Properties of Plasma-Enhanced Atomic Layer Deposited Tungsten Films by Using Tungsten Chloride Precursors. , 2020, , .		0
51	Comparative Study of the Growth Characteristics and Electrical Properties of Atomic-layer-deposited W Films Obtained from Newly Synthesized Metalorganic and Halide Precursor. , 2020, , .		0
52	Synthesis of two-dimensional MoS ₂ /graphene heterostructure by atomic layer deposition using MoF ₆ precursor. Applied Surface Science, 2019, 494, 591-599.	6.1	25
53	Porous Metal-Organic Framework CUK-1 for Adsorption Heat Allocation toward Green Applications of Natural Refrigerant Water. ACS Applied Materials & Interfaces, 2019, 11, 25778-25789.	8.0	45
54	Improved Sensitivity in Schottky Contacted Two-Dimensional MoS ₂ Gas Sensor. ACS Applied Materials & Interfaces, 2019, 11, 38902-38909.	8.0	117

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55	Selectivity Modulated by Surface Ligands on Cu ₂ O/TiO ₂ Catalysts for Gas-Phase Photocatalytic Reduction of Carbon Dioxide. <i>Journal of Physical Chemistry C</i> , 2019, 123, 29184-29191.	3.1	27
56	Activity Origin and Multifunctionality of Pt-Based Intermetallic Nanostructures for Efficient Electrocatalysis. <i>ACS Catalysis</i> , 2019, 9, 11242-11254.	11.2	96
57	Thickness-dependent electrochemical response of plasma enhanced atomic layer deposited WS ₂ anodes in Na-ion battery. <i>Electrochimica Acta</i> , 2019, 322, 134766.	5.2	18
58	Textile-based high-performance hydrogen evolution of low-temperature atomic layer deposition of cobalt sulfide. <i>Nanoscale</i> , 2019, 11, 844-850.	5.6	17
59	Hydrogen barrier performance of sputtered La ₂ O ₃ films for InGaZnO thin-film transistor. <i>Journal of Materials Science</i> , 2019, 54, 11145-11156.	3.7	18
60	Moisture barrier properties of low-temperature atomic layer deposited Al ₂ O ₃ using various oxidants. <i>Ceramics International</i> , 2019, 45, 19105-19112.	4.8	11
61	Ligand-Controlled Direct Hydroformylation of Trisubstituted Olefins. <i>Organic Letters</i> , 2019, 21, 5789-5792.	4.6	17
62	Experimental and Density Functional Theory Corroborated Optimization of Durable Metal Embedded Carbon Nanofiber for Oxygen Electrocatalysis. <i>Journal of Physical Chemistry Letters</i> , 2019, 10, 3109-3114.	4.6	16
63	Out-of-plane piezoresponse of monolayer MoS ₂ on plastic substrates enabled by highly uniform and layer-controllable CVD. <i>Applied Surface Science</i> , 2019, 487, 1356-1361.	6.1	36
64	Phase-controlled synthesis of SnO _x thin films by atomic layer deposition and post-treatment. <i>Applied Surface Science</i> , 2019, 480, 472-477.	6.1	25
65	Low-temperature, high-growth-rate ALD of SiO ₂ using aminodisilane precursor. <i>Applied Surface Science</i> , 2019, 485, 381-390.	6.1	27
66	Light Emission Enhancement by Tuning the Structural Phase of APbBr ₃ (A = Tl, ET, Q, O, O, rg, BT, /Overlock, 10 Tf, 50, 307 Td) 2135-2142.	4.6	12
67	Enthalpy-Entropy Interplay in π -Stacking Interaction of Benzene Dimer in Water. <i>Journal of Chemical Theory and Computation</i> , 2019, 15, 1538-1545.	5.3	16
68	Bi-layer high- κ dielectrics of Al ₂ O ₃ /ZrO ₂ to reduce damage to MoS ₂ channel layers during atomic layer deposition. <i>2D Materials</i> , 2019, 6, 015019.	4.4	12
69	Probing Surface Chemistry at an Atomic Level: Decomposition of 1-Propanethiol on GaP(001) (2 Å–4) Investigated by STM, XPS, and DFT. <i>Journal of Physical Chemistry C</i> , 2019, 123, 2964-2972.	3.1	0
70	Atomic Layer Deposition of Al ₂ O ₃ with Alcohol Oxidants for Impeding Substrate Oxidation. <i>ECS Meeting Abstracts</i> , 2019, . .	0.0	0
71	Hydrogen Barrier Properties of Atomic Layer Deposited Al ₂ O ₃ with Different Oxidants for IngaZno Thin Film Transistor. <i>ECS Meeting Abstracts</i> , 2019, MA2019-02, 1129-1129.	0.0	2
72	Interlayer-assisted atomic layer deposition of MgO as a magnetic tunneling junction insulators. <i>Journal of Alloys and Compounds</i> , 2018, 747, 505-510.	5.5	7

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73	Improved Synapse Device With MLC and Conductance Linearity Using Quantized Conduction for Neuromorphic Systems. IEEE Electron Device Letters, 2018, 39, 312-315.	3.9	60
74	High-Performance Ink-Synthesized Cu-Gate Thin-Film Transistor with Diffusion Barrier Formation. Metals and Materials International, 2018, 24, 652-656.	3.4	1
75	Cluster Expansion Method for Simulating Realistic Size of Nanoparticle Catalysts with an Application in CO ₂ Electroreduction. Journal of Physical Chemistry C, 2018, 122, 9245-9254.	3.1	17
76	Polymeric Carbon Nitride with Localized Aluminum Coordination Sites as a Durable and Efficient Photocatalyst for Visible Light Utilization. ACS Catalysis, 2018, 8, 4241-4256.	11.2	118
77	Mixed Valence Perovskite Cs ₂ Au ₂ I ₆ : A Potential Material for Thin-Film Pb-Free Photovoltaic Cells with Ultrahigh Efficiency. Advanced Materials, 2018, 30, e1707001.	21.0	79
78	Insight into the Microenvironments of the Metal-Ionic Liquid Interface during Electrochemical CO ₂ Reduction. ACS Catalysis, 2018, 8, 2420-2427.	11.2	77
79	Exfoliated 2D Lepidocrocite Titanium Oxide Nanosheets for High Sulfur Content Cathodes with Highly Stable Li-S Battery Performance. ACS Energy Letters, 2018, 3, 412-419.	17.4	90
80	Enhanced Light Stability of InGaZnO Thin-Film Transistors by Atomic-Layer-Deposited Y ₂ O ₃ with Ozone. ACS Applied Materials & Interfaces, 2018, 10, 2143-2150.	8.0	41
81	Water-Erasable Memory Device for Security Applications Prepared by the Atomic Layer Deposition of GeO ₂ . Chemistry of Materials, 2018, 30, 830-840.	6.7	15
82	Hydrogen plasma-enhanced atomic layer deposition of hydrogenated amorphous carbon thin films. Surface and Coatings Technology, 2018, 344, 12-20.	4.8	9
83	Ga-Doped Pt-Ni Octahedral Nanoparticles as a Highly Active and Durable Electrocatalyst for Oxygen Reduction Reaction. Nano Letters, 2018, 18, 2450-2458.	9.1	125
84	Multiscale Simulation Method for Quantitative Prediction of Surface Wettability at the Atomistic Level. Journal of Physical Chemistry Letters, 2018, 9, 1750-1758.	4.6	23
85	Bifunctional 2D Superlattice Electrocatalysts of Layered Double Hydroxide-Transition Metal Dichalcogenide Active for Overall Water Splitting. ACS Energy Letters, 2018, 3, 952-960.	17.4	140
86	Cobalt titanium nitride amorphous metal alloys by atomic layer deposition. Journal of Alloys and Compounds, 2018, 737, 684-692.	5.5	5
87	Input-Splitting of Large Neural Networks for Power-Efficient Accelerator with Resistive Crossbar Memory Array. , 2018, , .		17
88	Roles of SnX ₂ (X = F, Cl, Br) Additives in Tin-Based Halide Perovskites toward Highly Efficient and Stable Lead-Free Perovskite Solar Cells. Journal of Physical Chemistry Letters, 2018, 9, 6024-6031.	4.6	121
89	Superior role of MXene nanosheet as hybridization matrix over graphene in enhancing interfacial electronic coupling and functionalities of metal oxide. Nano Energy, 2018, 53, 841-848.	16.0	36
90	Effects of Ar Addition to O ₂ Plasma on Plasma-Enhanced Atomic Layer Deposition of Oxide Thin Films. ACS Applied Materials & Interfaces, 2018, 10, 40286-40293.	8.0	14

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91	High-Performance Gas Sensor Using a Large-Area WS ₂ Se ₂ Alloy for Low-Power Operation Wearable Applications. ACS Applied Materials & Interfaces, 2018, 10, 34163-34171.	8.0	93
92	Simultaneous improvement of the dielectric constant and leakage currents of ZrO ₂ dielectrics by incorporating a highly valent Ta ⁵⁺ element. Journal of Materials Chemistry C, 2018, 6, 9794-9801.	5.5	13
93	Recovery Improvement for Large-Area Tungsten Diselenide Gas Sensors. ACS Applied Materials & Interfaces, 2018, 10, 23910-23917.	8.0	115
94	Comparative study of the growth characteristics and electrical properties of atomic-layer-deposited HfO ₂ films obtained from metal halide and amide precursors. Journal of Materials Chemistry C, 2018, 6, 7367-7376.	5.5	40
95	Molecular oxidation of surface -CH ₃ during atomic layer deposition of Al ₂ O ₃ with H ₂ O, H ₂ O ₂ , and O ₃ : A theoretical study. Applied Surface Science, 2018, 457, 376-380.	6.1	29
96	Structural and electrical properties of Ge-doped ZrO ₂ thin films grown by atomic layer deposition for high-k dielectrics. Journal of Materials Science, 2018, 53, 15237-15245.	3.7	18
97	Low-temperature direct synthesis of high quality WS ₂ thin films by plasma-enhanced atomic layer deposition for energy related applications. Applied Surface Science, 2018, 459, 596-605.	6.1	42
98	Low-temperature synthesis of 2D MoS ₂ on a plastic substrate for a flexible gas sensor. Nanoscale, 2018, 10, 9338-9345.	5.6	142
99	Molecular Identification of Cr(VI) Removal Mechanism on Vivianite Surface. Environmental Science & Technology, 2018, 52, 10647-10656.	10.0	53
100	Amorphous TiO ₂ /p-Si Heterojunction Photodiode Prepared by Low-Temperature Atomic Layer Deposition. Nanoscience and Nanotechnology Letters, 2018, 10, 800-804.	0.4	2
101	Surface Wettability of Nitrogen-Doped TiO ₂ Films Prepared by Atomic Layer Deposition Using NH ₄ OH as the Doping Source. Nanoscience and Nanotechnology Letters, 2018, 10, 779-783.	0.4	1
102	A composite layer of atomic-layer-deposited Al ₂ O ₃ and graphene for flexible moisture barrier. Carbon, 2017, 116, 553-561.	10.3	45
103	Growth behavior of Bi ₂ Te ₃ and Sb ₂ Te ₃ thin films on graphene substrate grown by plasma-enhanced chemical vapor deposition. Physica Status Solidi - Rapid Research Letters, 2017, 11, 1600369.	2.4	11
104	Polymorphic Phase Control Mechanism of Organic-Inorganic Hybrid Perovskite Engineered by Dual-Site Alloying. Journal of Physical Chemistry C, 2017, 121, 9508-9515.	3.1	16
105	Improvement of thermoelectric properties of Bi ₂ Te ₃ and Sb ₂ Te ₃ films grown on graphene substrate. Physica Status Solidi - Rapid Research Letters, 2017, 11, 1700029.	2.4	14
106	Comparative study on growth characteristics and electrical properties of ZrO ₂ films grown using pulsed plasma-enhanced chemical vapor deposition and plasma-enhanced atomic layer deposition for oxide thin film transistors. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, 031510.	2.1	4
107	Facile CO ₂ Electro-Reduction to Formate via Oxygen Bidentate Intermediate Stabilized by High-Index Planes of Bi Dendrite Catalyst. ACS Catalysis, 2017, 7, 5071-5077.	11.2	263
108	Atomic layer deposition of Y-stabilized ZrO ₂ for advanced DRAM capacitors. Journal of Alloys and Compounds, 2017, 722, 307-312.	5.5	40

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109	Fabrication of single-phase SnS film by H ₂ annealing of amorphous SnS _x prepared by atomic layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017, 35, .	2.1	17
110	Growth mechanism of Co thin films formed by plasma-enhanced atomic layer deposition using NH ₃ as plasma reactant. <i>Current Applied Physics</i> , 2017, 17, 333-338.	2.4	14
111	Distorted Carbon Nitride Structure with Substituted Benzene Moieties for Enhanced Visible Light Photocatalytic Activities. <i>ACS Applied Materials & Interfaces</i> , 2017, 9, 40360-40368.	8.0	80
112	Atomistic Simulation Protocol for Improved Design of SiO ₂ /C Hybrid Nanostructures as Li-Ion Battery Anodes: ReaxFF Reactive Force Field. <i>Journal of Physical Chemistry C</i> , 2017, 121, 23268-23275.	3.1	14
113	Catalytic chemical vapor deposition of large-area uniform two-dimensional molybdenum disulfide using sodium chloride. <i>Nanotechnology</i> , 2017, 28, 465103.	2.6	42
114	New Features and Uncovered Benefits of Polycrystalline Magnetite as Reusable Catalyst in Reductive Chemical Conversion. <i>Journal of Physical Chemistry C</i> , 2017, 121, 25195-25205.	3.1	15
115	Micropatternable Double-Faced ZnO Nanoflowers for Flexible Gas Sensor. <i>ACS Applied Materials & Interfaces</i> , 2017, 9, 32876-32886.	8.0	147
116	Surface-Localized Sealing of Porous Ultralow- <i>k</i> Dielectric Films with Ultrathin (≤ 2 nm) Polymer Coating. <i>ACS Nano</i> , 2017, 11, 7841-7847.	14.6	19
117	The Impact of an Ultrathin Y ₂ O ₃ Layer on GeO ₂ Passivation in Ge MOS Gate Stacks. <i>IEEE Transactions on Electron Devices</i> , 2017, 64, 3303-3307.	3.0	19
118	Input Voltage Mapping Optimized for Resistive Memory-Based Deep Neural Network Hardware. <i>IEEE Electron Device Letters</i> , 2017, 38, 1228-1231.	3.9	37
119	Atomic-scale characterization of plasma-induced damage in plasma-enhanced atomic layer deposition. <i>Applied Surface Science</i> , 2017, 425, 781-787.	6.1	6
120	Transfer and Dynamic Inversion of Coassembled Supramolecular Chirality through 2D-Sheet to Rolled-Up Tubular Structure. <i>Journal of the American Chemical Society</i> , 2017, 139, 17711-17714.	13.7	62
121	Reaction Mechanism of Area-Selective Atomic Layer Deposition for Al ₂ O ₃ Nanopatterns. <i>ACS Applied Materials & Interfaces</i> , 2017, 9, 41607-41617.	8.0	73
122	Highly Uniform Atomic Layer-Deposited MoS ₂ @3D-Ni-Foam: A Novel Approach To Prepare an Electrode for Supercapacitors. <i>ACS Applied Materials & Interfaces</i> , 2017, 9, 40252-40264.	8.0	117
123	Zinc-Phosphorus Complex Working as an Atomic Valve for Colloidal Growth of Monodisperse Indium Phosphide Quantum Dots. <i>Chemistry of Materials</i> , 2017, 29, 6346-6355.	6.7	53
124	Uniform color coating of multilayered TiO ₂ /Al ₂ O ₃ films by atomic layer deposition. <i>Journal of Coatings Technology Research</i> , 2017, 14, 177-183.	2.5	4
125	Self-Limiting Layer Synthesis of Transition Metal Dichalcogenides. <i>Scientific Reports</i> , 2016, 6, 18754.	3.3	74
126	Comparison of hydrogen sulfide gas and sulfur powder for synthesis of molybdenum disulfide nanosheets. <i>Current Applied Physics</i> , 2016, 16, 691-695.	2.4	15

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127	High efficiency n-Si/p-Cu ₂ O core-shell nanowires photodiode prepared by atomic layer deposition of Cu ₂ O on well-ordered Si nanowires array. <i>Electronic Materials Letters</i> , 2016, 12, 404-410.	2.2	14
128	Effects of TaN Diffusion Barrier on Cu-Gate ZnO:N Thin-Film Transistors. <i>IEEE Electron Device Letters</i> , 2016, 37, 599-602.	3.9	4
129	Very high frequency plasma reactant for atomic layer deposition. <i>Applied Surface Science</i> , 2016, 387, 109-117.	6.1	13
130	Effect of Al ₂ O ₃ Deposition on Performance of Top-Gated Monolayer MoS ₂ -Based Field Effect Transistor. <i>ACS Applied Materials & Interfaces</i> , 2016, 8, 28130-28135.	8.0	40
131	Improvement of Gas-Sensing Performance of Large-Area Tungsten Disulfide Nanosheets by Surface Functionalization. <i>ACS Nano</i> , 2016, 10, 9287-9296.	14.6	351
132	Highly conductive and flexible fiber for textile electronics obtained by extremely low-temperature atomic layer deposition of Pt. <i>NPG Asia Materials</i> , 2016, 8, e331-e331.	7.9	51
133	Highly Flexible Hybrid CMOS Inverter Based on Si Nanomembrane and Molybdenum Disulfide. <i>Small</i> , 2016, 12, 5720-5727.	10.0	46
134	Flexible Electronics: Highly Flexible Hybrid CMOS Inverter Based on Si Nanomembrane and Molybdenum Disulfide (<i>Small</i> 41/2016). <i>Small</i> , 2016, 12, 5650-5650.	10.0	0
135	High-Throughput Screening to Investigate the Relationship between the Selectivity and Working Capacity of Porous Materials for Propylene/Propane Adsorptive Separation. <i>Journal of Physical Chemistry C</i> , 2016, 120, 24224-24230.	3.1	37
136	Formation of Ni silicide from atomic layer deposited Ni. <i>Current Applied Physics</i> , 2016, 16, 720-725.	2.4	4
137	Uniform, large-area self-limiting layer synthesis of tungsten diselenide. <i>2D Materials</i> , 2016, 3, 014004.	4.4	40
138	Static and Dynamic Performance of Complementary Inverters Based on Nanosheet In_2MoTe_2 p -Channel and MoS ₂ n -Channel Transistors. <i>ACS Nano</i> , 2016, 10, 1118-1125.	14.6	98
139	Growth characteristics and electrical properties of SiO ₂ thin films prepared using plasma-enhanced atomic layer deposition and chemical vapor deposition with an aminosilane precursor. <i>Journal of Materials Science</i> , 2016, 51, 5082-5091.	3.7	31
140	A Separate Extraction Method for Asymmetric Source and Drain Resistances Using Frequency-Dispersive C-V Characteristics in Exfoliated MoS ₂ FET. <i>IEEE Electron Device Letters</i> , 2016, 37, 231-233.	3.9	7
141	Effects of Cl-Based Ligand Structures on Atomic Layer Deposited HfO ₂ . <i>Journal of Physical Chemistry C</i> , 2016, 120, 5958-5967.	3.1	18
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